PbI₂ as a direct semiconductor for use in radiation imaging detectors

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Fluorescent & Scintillation Products for Industry, Science & Medicine



Overview

Motivation Why PbI₂? Material Processing Optical Spectroscopy Electrical Characteristics Perspectives Conclusion

Motivation

- Inexpensive (\$10-20/sq.in) deposition on an a-Si active matrix flat panel imager (AMFPI)
- Target market Medical x-ray fluoroscopy (visualisation on catheter and stent based procedures in primarily in thoracic areas)
- Direct detection reduces AMFPI costs by eliminating the photodiode component and significantly cutting extensive processing steps (e.g. GE/NIST)
- To reduce dark current value to <10 nA/cm²
- To reduce image lag for the high frame rate (30 fps) fluoroscopy applications

Why PbI₂?

- layered semiconductor, anisotropic
- hexagonal close packed (HCP)
- av. absorption coeff. 57 cm⁻¹
- k edges (88; 33.1)
- density, 6.2g/cm³
- band gap, 2.55eV indicates that devices should operate a low leakage currents at high temperature.
- carrier mobilities
 - electrons 8 cm²/V s
 - holes $2 \text{ cm}^2/\text{V} \text{ s}$
- μτ
 - 10⁻⁵ cm²/V – electrons
 - holes 2.10⁻⁶ cm²/V
- conversion efficiency approx.240 e^{-}/keV (~5 eV/e^{-})

conversion efficiency x5 CsI:Tl, Gd₂O₂S:Tb x10 a-Se



Who has investigated lead iodideand for what application?

Nuclear spectrometers

- Radiation Monitoring Devices, Inc (RMD) Watertown, MA, US
- Tohoku University, Japan
- Hebrew University of Jerusalem,
- Fisk University, Nashville, TN, US
- University of Bari, Italy
- SiemensAG, Erlangen, Germany

- K.Shah et al (1990's)
- T.Shoji et al (1990's -
- M. Roth et al (1980's)
- A. Burger (1980's)
- C. Manfredotti (1977)
- S. Roth and W.R. Willig (1971)
- Advanced solid state batteries (Ionic Conductivity)
- Sandia National Labs, Albuquerque, NM, US
- University of Illinois, Urbana-Champaign, IL, US
- Image recording and high resolution photography
- University of Bristol, UK

- G.A. Samara(1970's/80's)
- J. Oberschmidt (1970's/80's)
- A.J. Forty et al (1950's-1960's)

A process for manufacture of PbI₂ thick films



Purification (zone refining)

- initial high quality feedstock
- high level of purification (ppb)

Thick film deposition

- semiconductor cleanliness
- control of polycrystallinity
- control of stoichiometry

Compression

- even compression, contact method
- what effects does it have on structure and polytype formation (XRD). Spectroscopy

Zone refining



• RF heating enables larger diameter quartz ampoules to be used; therefore larger batches of purified Pbl₂

Encapsulating chamber allows vacuum or inert gas environment; therefore can be used for removing volatile components prior to zoning when ampoule is not enclosed
Evolving design of graphite susceptors to optimise zoning process.

Deposition system



- Large area deposition system for PbI2 on amorphous silicon flat panels
- box system w24" x h30" x d30"

• front door, allows easy access and maintenance of source, shields, substrate mounting, etc.

- allows large panel deposition
- cryopump for clean pumping
- mass spectrometer for process control and quality/reproducibility monitoring

 side mounted pumping for ease of access to source heat, feedthroughs, substrate.

• provision for additional gas lines, iodine compensation, annealing, etc.

 provision for high pressure analysis with differentially pumped mass analyser

Surface morphology of lead iodide films



Film thickness variable $100 - 500 \ \mu m$

Compression Increases density Reduce voids Increases microcrystallite contact

What effect does compression have on the optical and electrical characteristics of the layer?

Low temperature (10K) photoluminescence



Photoluminescence spectra of high quality lead iodide (zone refined) I



Photoluminescence spectra of high quality lead iodide (zone refined) II



Low temperature photoluminescence of compressed PbI₂



Electrical measurements

- Dark current
- I-t
- I-V
- C-V



Dark current measurements



Time (s)

Post-processed PbI₂ 1 nA/cm²

Dielectric interlayer (Parylene) 100 pA/cm²

Semiconductor contacts



graphite

PbI₂ breakdown from underside of contact

Material choice dictates contact stability, e.g. Ag promotes rapid failure; Au, Te and colloidal graphite

Other failure modes





- Device drive conditions (V/cm⁻¹)
- Operational temperatures
- Other material impurities

EDX spectra of films



Contact stability in conditions with minimal potassium contamination

Perpectives

Project ceased due to reorganisation of key account partner

- Further work is required to optimise contact technology and drive characteristics
- IP for process in progess
- Key account partner being sought for taking project development to the next stage ...any offers???

Conclusions

Cost effective large area deposition achieved

Compression proven to be ineffective for high quality imaging layers

excessive deep level trapping resulting in image lag

Dark current targets achieved and exceeded

Optimum drive conditions and ultimate performance not yet established

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Thank you for listeningany questions?



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